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ATTORNEY DOCKET NO. CONFIRMATION NO. FIRST NAMED INVENTOR FILING DATE APPLICATION NO. 1275

10200/88 Sundar Narayanan 09/753,011 01/02/2001

07/18/2002 757 7590 **BRINKS HOFER GILSON & LIONE** P.O. BOX 10395 CHICAGO, IL 60610

EXAMINER MITCHELL, JAMES M

ART UNIT PAPER NUMBER

DATE MAILED: 07/18/2002

2827

Please find below and/or attached an Office communication concerning this application or proceeding.

		Application No.	Applicant(s)
		09/753,011	NARAYANAN, SUNDAR
. •	Office Action Summary 🔨	Examiner	Art Unit
	Office Action Cammary	James Mitchell	2827
	- The MAILING DATE of this communication a		
Period for	r Reply		
THE N - Exten after S - If the - If NO - Failur - Any re	ORTENED STATUTORY PERIOD FOR REIMAILING DATE OF THIS COMMUNICATION Isions of time may be available under the provisions of 37 CFR SIX (6) MONTHS from the mailing date of this communication. Period for reply specified above is less than thirty (30) days, a period for reply is specified above, the maximum statutory per to reply within the set or extended period for reply will, by stately received by the Office later than three months after the mandal patent term adjustment. See 37 CFR 1.704(b).	N. 1.136(a). In no event, however, may reply within the statutory minimum of t iod will apply and will expire SIX (6) Meture, cause the application to become	a reply be timely filed hirty (30) days will be considered timely. ONTHS from the mailing date of this communication. ABANDONED (35 U.S.C. § 133).
1)⊠	Responsive to communication(s) filed on 2	15 March 2002 .	
2a)□	This action is FINAL . 2b)⊠	This action is non-final.	
3)	Since this application is in condition for all	owance except for formal n	natters, prosecution as to the merits is
•	closed in accordance with the practice und ion of Claims		C.D. 11, 455 C.G. 215.
	Claim(s) 1-23 is/are pending in the applica		
	4a) Of the above claim(s) is/are with	drawn from consideration.	
5)[Claim(s) is/are allowed.		
6)⊠	Claim(s) <u>1-23</u> is/are rejected.		
	Claim(s) is/are objected to.		
_	Claim(s) are subject to restriction a	nd/or election requirement.	
• -	tion Papers	!	
9)[The specification is objected to by the Exar	miner.	by the Evaminer
10)	The drawing(s) filed on is/are: a)	accepted or b) objected to	boyance See 37 CFR 1.85(a)
	Applicant may not request that any objection	to the drawing(s) be neid in a	disapproved by the Examiner.
11)	The proposed drawing correction filed on _		disapproved by the Examiner.
	If approved, corrected drawings are required		
1	The oath or declaration is objected to by th	e Examiner.	
Priority	under 35 U.S.C. §§ 119 and 120		O C 440(a) (d) or (f)
1	Acknowledgment is made of a claim for fo	oreign priority under 35 U.S	.C. 9 119(a)-(d) or (1).
а	ı) ☐ All b) ☐ Some * c) ☐ None of:		
	1. Certified copies of the priority docu	ments have been received.	. A Bashan Na
	2. Certified copies of the priority docu	ments have been received	in Application No
	3. Copies of the certified copies of the application from the Internation See the attached detailed Office action for	al Bureau (PC) Ruie 17.2(a)).
14)	14) Acknowledgment is made of a claim for domestic priority under 35 U.S.C. § 119(e) (to a provisional application).		
	a) The translation of the foreign language] Acknowledgment is made of a claim for do	ge provisional application h	as been received.
Attachm			
1) NO	otice of References Cited (PTO-892) otice of Draftsperson's Patent Drawing Review (PTO-9 formation Disclosure Statement(s) (PTO-1449) Paper I	48) 5) Noti	rview Summary (PTO-413) Paper No(s) ice of Informal Patent Application (PTO-152) er:

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DETAILED ACTION

1. This office action is in response to the amendment filed March 15, 2002.

Drawings

2. Figures 1-5 should be designated by a legend such as —Prior Art-- because only that which is old is illustrated. See MPEP § 608.02(g). A proposed drawing correction or corrected drawings are required in reply to the Office action to avoid abandonment of the application. The objection to the drawings will not be held in abeyance.

Claim Rejections - 35 USC § 102

3. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (e) the invention was described in-
- (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effect under this subsection of a national application published under section 122(b) only if the international application designating the United States was published under Article 21(2)(a) of such treaty in the English language; or
- (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that a patent shall not be deemed filed in the United States for the purposes of this subsection based on the filing of an international application filed under the treaty defined in section 351(a).
- 4. Claims 1-7, 9-19 and 21 are rejected under 35 U.S.C. 102(e) as being anticipated by Wu (U.S 6,410,403).
- 5. Wu (Fig 2-6) discloses a method of forming a semiconductor structure or device (Column 1, Lines 7-8) comprising: forming an isolation region (30) by etching a trench in a semiconductor substrate (10), wherein a first oxide layer (14) is on said substrate, a first oxide sacrificial layer comprising an oxide (22) on said first oxide layer, and a first or isolation nitride layer (24; Column 5, Lines 50-51) is on said first sacrificial layer having

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thickness greater than said first and a silicon nitride second sacrificial layer (18) on said first sacrificial layer; wherein a second sacrificial layer is between said first sacrificial layer and said first oxide; with said isolation regions comprising an oxide (34); removing said first nitride layer, said first sacrificial layer and said second sacrificial layer (shown in Fig 4-5); inherently implanting ions in said substrate (Column 3, Lines 17-18); depositing an oxide (34) onto said first nitride and onto a trench adjacent to a said first nitride layer, said first sacrificial layer and said first oxide layer; wherein said first sacrificial layer is between said isolation nitride and said substrate and said first sacrificial layer has a thickness of 10 to 250 Angstrom (Column 6, Lines 1-2); and forming an electronic device comprising said semiconductor device.

Claim Rejections - 35 USC § 103

- 6. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 7. This application currently names joint inventors. In considering patentability of the claims under 35 U.S.C. 103(a), the examiner presumes that the subject matter of the various claims was commonly owned at the time any inventions covered therein were made absent any evidence to the contrary. Applicant is advised of the obligation under 37 CFR 1.56 to point out the inventor and invention dates of each claim that was not commonly owned at the time a later invention was made in order for the examiner to

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consider the applicability of 35 U.S.C. 103(c) and potential 35 U.S.C. 102(e), (f) or (g) prior art under 35 U.S.C. 103(a).

- 8. Claims 8, 22 and 23 are rejected under 35 U.S.C. 103(a) as being unpatentable over Wu as applied to claims 3, 7 and 21 are further in combination with Ibok (U.S 6,391,784).
- 9. Wu does not explicitly disclose that said first sacrificial oxide layer is formed by thermal oxidation or that said oxide layer is silicon oxide, however lbok teaches the use of thermal oxidation and an oxide layer comprising silicon oxide.
- 10. It would have been obvious to one of ordinary skill in the art to form the oxide layer of Wu by thermal oxidation to form silicon oxide in order to provide an oxide layer as taught by lbok (Column 1, Lines 24-25; Column 4, Lines 42-43).

Conclusion

11. Any inquiry concerning this communication or earlier communications from the examiner should be directed to James Mitchell whose telephone number is (703) 305-0244. The examiner can normally be reached on M-F 10:30-8:00.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, David L. Talbott can be reached on (703) 305-9883. The fax phone numbers for the organization where this application or proceeding is assigned are (703) 305-3432 for regular communications and (703) 305-3230 for After Final communications.

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Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is (703) 308-0956.

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July 15, 2002

Ottober Polai 7-15-62

ALBERT W. PALADINI PRIMARY EXAMINER